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520.43079X00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: TANAKA et al

Serial No.: 10/648,231

Filed: August 27, 2003

For: System And Method For Evaluating A Semiconductor
Device Pattern, Method For Controlling Process Of Forming
A Semiconductor Device Pattern And Method For Monitoring
A Semiconductor Device Manufacturing Process

Art Unit: 285

Examiner: T. To

RESPONSE

Mail Stop: Response (No Fee)
Commissioner For Patents
P.O. Box 1450
Alexandria, VA 22313-1450

April 18, 2006

Sir:

The following remarks are respectfully submitted in connection with the
above-identified application, in response to the Office Action dated March 23, 2006.

In response to the requirement to elect one of the alleged following patentably
distinct species of the claimed invention, identified by the Examiner, as Group I -
claims 1 - 16, drawn to methods and systems for evaluating a semiconductor device
pattern, and Group II - claims 17 and 18, drawn to a method for controlling and
monitoring a pattern forming process, applicants elect Group I including claims
1 - 16, as identified by the Examiner.

In light of the election of Group I, including claims 1 - 16, applicants request
favorable action thereon.